

REMARKS

In view of the above amendments and the following remarks, reconsideration of the rejections contained in the Office Action of January 9, 2008 is respectfully requested.

By this Amendment, claims 1, 4 and 6 have been amended, and claims 2, 3 and 8-12 have been cancelled. Thus, claims 1 and 4-7 are currently pending in the application. No new matter has been added by these amendments.

On pages 2-4 of the Office Action, the Examiner rejected claims 1-11 under 35 U.S.C. § 102(b) as being anticipated by Fujitani et al. (JP 2003-054991). For the reasons discussed below, it is respectfully submitted that the amended claims are clearly patentable over the prior art of record.

Amended independent claim 1 recites a plasma display panel comprising a front panel including a display electrode, a dielectric layer and a protective layer sequentially formed on a first glass substrate, and a back panel confronting the front panel and including an address electrode, a base dielectric layer, a barrier rib and a phosphor layer sequentially formed on a second glass substrate. Claim 1 also recites that the front panel and the back panel are disposed so as to confront each other and being sealed at outer walls of the front panel and the back panel with a sealing member *so as to form an inner space between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel*. Claim 1 also recites *a catalyst provided on at least one of the base dielectric layer, the barrier rib and the phosphor layer so as to be exposed to the inner space and react with a hydrocarbon existing in the inner space*.

Fujitani discloses a plasma display panel (PDP) which, as shown in Fig. 1, includes a front panel 101 and a back panel 111. The front panel 101 includes a dielectric layer 104, and a protective layer 105 covering the dielectric layer 104.

However, Fujitani does not disclose that the front panel and the back panel are disposed so as to confront each other and being sealed at outer walls of the front panel and the back panel with a sealing member *so as to form an inner space between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel*, with a catalyst being provided *on at least one of the base dielectric layer, the barrier rib and the*

phosphor layer so as to be exposed to the inner space and react with a hydrocarbon existing in the inner space, as required by amended independent claim 1. Rather, Fujitani discloses that the dielectric layer 104 is made from a dielectric layer precursor 104a, which as shown in Fig. 4 includes glass powder 1040, a dispersant 1041 and a decomposition accelerating material 1042. As explained in paragraph [0012], Fujitani discloses that due to the decomposition accelerating material, organic material (such as resin in the dispersant) is decomposed quickly such that when the glass powder is melted to form the dielectric layer 104, gas generated from the decomposition of the organic material will not become trapped in the resulting dielectric layer 104.

In this regard, it is noted that Fujitani does not disclose a catalyst being provided on at least one of the base dielectric layer, the barrier rib and the phosphor layer of the back panel, as required by claim 1, because Fujitani only discloses the catalyst being provided in a dielectric layer of the front panel.

Further, Fujitani does not disclose a catalyst provided on at least one of the base dielectric layer, the barrier rib and the phosphor layer *so as to be exposed to an inner space defined between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel*, as required by independent claim 1. Rather, as shown in Fig. 1, Fujitani discloses that the dielectric layer 104 is covered by the protective layer 105, and therefore the dielectric layer 104 is not exposed to an inner space between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel. Thus, any catalyst contained in the dielectric layer 104 is also not exposed to the inner space, as required by independent claim 1.

Further, as indicated above, it is noted that the plasma display panel of amended independent claim 1 includes *a front panel having a protective layer*, and that the front panel and the back panel are disposed so as to confront each other and are sealed at outer walls of the front panel and the back panel with a sealing member *so as to form an inner space between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel*. Fujitani, however, discloses that the catalyst is utilized during the formation of the dielectric layer (*i.e., prior* to the formation of the protective layer and the sealing of the front and back panels). Therefore, Fujitani does not disclose a catalyst to be exposed to an inner space.

formed between the protective layer of the front panel and the phosphor layer, barrier rib and base dielectric layer of the back panel, with the front panel and back panel being disposed so as to confront each other and sealed at outer walls of the front panel and the back panel with a sealing member, because Fujitani discloses that the catalyst is utilized prior to the formation of the protective layer, and therefore discloses a catalyst being exposed to a space which is not defined by the protective layer of the front panel. Additionally, Fujitani discloses a catalyst being exposed to a space while forming the dielectric layer on a front panel which is not yet sealed with a back panel by a sealing member.

In addition, Fujitani only discloses a decomposition accelerating material by which organic material (such as resin in the dispersant) is decomposed quickly such that when glass powder is melted to form the dielectric layer, gas generated from the decomposition of the organic material will not become trapped in the resulting dielectric layer, and does not disclose *a catalyst to be exposed to the inner space and react with a hydrocarbon existing in the inner space*, as required by independent claim 1.

Therefore, it is respectfully submitted that independent claim 1, as well as claims 4-7 which depend therefrom, are clearly allowable over the prior art of record.

In view of the foregoing amendments and remarks, it is respectfully submitted that the present application is clearly in condition for allowance. An early notice to that effect is respectfully solicited.

If, after reviewing this Amendment, the Examiner feels there are any issues remaining which must be resolved before the application can be passed to issue, the Examiner is respectfully requested to contact the undersigned by telephone in order to resolve such issues.

Respectfully submitted,

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By: Pledger/

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